

Glow Discharge Proc

SPUTTERING AND PLASMA ETCHING

Brian Chapman

A WILEY-INTERSCIENCE PUBLICATION

JOHN WILEY & SONS

New York • Chichester • Brisbane • Toronto • Si

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Library of Congress Cataloging in Publication

Chapman, Brian N

Glow discharge processes.

“A Wiley-Interscience publication.”

Includes bibliographical references and index.

1. Sputtering (Physics) 2. Glow discharge.

I. Title. II. Title: Plasma etching.

QC702.7.P6C48 537.5'2 80-

ISBN 0-471-07828-X

Printed in the United States of America

20 19 18 17 16 15 14 13

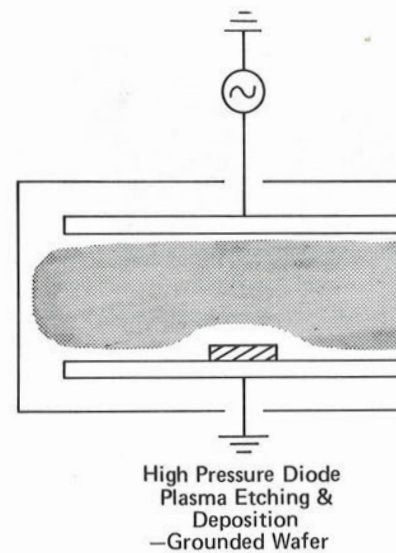


Figure 7-23. High pressure diode plasma etching and deposition.

quarter of the applied rf peak-to-peak voltage (Chapter 7) — 250 V for practical plasma etching processes. This is determined by measurements and by observation of the dark spaces formed. The energy of ion bombardment on an electrode is determined by the sheath thickness and by collisions in the sheath, as discussed in Chapters 7 and 8.

Reactive ion etching systems (Figure 7-24) are essentially sputtering systems. In sputtering, intense ion bombardment at the target is confined to the target area and nowhere else. This is achieved by making the target area a small fraction of the grounded chamber and baseplate. As a result, the sheath at the target is very small, but the sheath at the chamber walls is much larger. The sheath at the target, and hence at the chamber walls, is very thin, amounting typically to ~300 V.

The different operating pressures of the two diode systems result in ion bombardment energies very greatly, because the ion mean free path at the higher pressure is offset by the much thinner dark space sheath. The two effects would